

10/069656

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[20103 00201]

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s) : SMIRNOV et al.
Serial No. : To Be Assigned
Filed : Herewith
For : DEVICE FOR FORMING NANOSTRUCTURES ON THE
SURFACE OF A SEMICONDUCTOR WAFER BY MEANS
OF ION BEAMS
Art Unit : To Be Assigned
Examiner : To Be Assigned

Commissioner for Patents
Washington, D.C. 20231

**PRELIMINARY AMENDMENT AND
37 C.F.R. § 1.125 SUBSTITUTE SPECIFICATION STATEMENT**

SIR:

Please amend the above-identified application before examination, as set forth below.

IN THE SPECIFICATION AND ABSTRACT:

In accordance with 37 C.F.R. § 1.121(b)(3), a Substitute Specification (including the Abstract, but without claims) accompanies this response. It is respectfully requested that the Substitute Specification (including Abstract) be entered to replace the Specification of record.

IN THE CLAIMS:

Without prejudice, please cancel original claims 1 -- 3, and please add new claims 4 -- 8 as follows:

4. (New) A system for forming nanostructures on a surface of a semiconductor wafer, comprising:
 - a. a vacuum chamber having exhaust and annealing systems;
 - b. an input device inputting a semiconductor wafer into the vacuum chamber;